

Title (en)

EXPOSURE DEVICE FOR THE STRUCTURED EXPOSURE OF A SURFACE

Title (de)

BELICHTUNGSEINRICHTUNG ZUR STRUKTURIERTEN BELICHTUNG EINER FLÄCHE

Title (fr)

DISPOSITIF D'ÉCLAIRAGE POUR L'ÉCLAIRAGE STRUCTURÉ D'UNE SURFACE

Publication

EP 2695015 A1 20140212 (DE)

Application

EP 12722065 A 20120308

Priority

- DE 102011001785 A 20110404
- DE 2012100056 W 20120308

Abstract (en)

[origin: WO2012136199A1] The invention relates to an exposure device (14) for the structured exposure of a wafer, comprising at least one exposure arrangement (13) with which a beam (2) that is separated into two sub-beams (2.1, 2.2) is modulated via two micromirror arrays (5.1; 5.2) in order to increase the throughput speed during the exposure of wafers.

IPC 8 full level

G02B 26/08 (2006.01); **G03F 7/20** (2006.01)

CPC (source: EP KR US)

G02B 3/0056 (2013.01 - EP KR US); **G02B 26/0841** (2013.01 - EP KR US); **G03F 7/7005** (2013.01 - EP KR US); **G03F 7/70058** (2013.01 - KR); **G03F 7/70208** (2013.01 - EP KR US); **G03F 7/70291** (2013.01 - EP KR US); **H01L 21/67069** (2013.01 - KR US)

Citation (search report)

See references of WO 2012136199A1

Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

DOCDB simple family (publication)

DE 102011001785 A1 20121004; **DE 102011001785 B4 20150305**; CN 103649815 A 20140319; EP 2695015 A1 20140212; JP 2014514759 A 20140619; JP 5965986 B2 20160810; KR 20140027136 A 20140306; TW 201241577 A 20121016; TW I537686 B 20160611; US 2014118711 A1 20140501; US 9110380 B2 20150818; WO 2012136199 A1 20121011

DOCDB simple family (application)

DE 102011001785 A 20110404; CN 201280017466 A 20120308; DE 2012100056 W 20120308; EP 12722065 A 20120308; JP 2014502991 A 20120308; KR 20137026435 A 20120308; TW 101103203 A 20120201; US 201213820399 A 20120308